## Amendments to the Claims

Claims 2, 12 - 17, 21, 40, 46 - 48, 51, and 52 without prejudice;

g listing of claims replaces all prior versions and listings of claims in

Amended) A substrate processing chamber comprising:

dy;

p disposed on the chamber body; and

re-coupled plasma generator plate within the substrate processing of transformer cores within the transformer-coupled plasma generator agh holes forming conduits from a first side of the transformerate to a second side of the transformer-coupled plasma generator passing through a first transformer core and a second of the conduits

ormer core.

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The substrate processing chamber of claim 1 wherein the plasma

Amended) The substrate processing chamber of claim 1 further former core within the transformer-coupled plasma generating by coil being is disposed to electro-magnetically couple to the first ad primary coil being is disposed to electro-magnetically couple to be within the transformer-coupled plasma generator plate, wherein execond primary coil are connected to each other in series.

Amended) The substrate processing chamber of claim 1 wherein e comprises ferrite material.

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- 6. (Original) The substrate processing chamber of claim 1 wherein the transformer-coupled plasma generator plate includes a dielectric spacer between the first side and the second side, and a remainder of an outer surface of the generator plate comprises an electrical conductor.
- 7. (Original) The substrate processing chamber of claim 6 wherein the dielectric spacer is disposed within a conduit through the transformer-coupled generator plate.
- 8. (Original) The substrate processing chamber of claim 1 further comprising an alternating-current power supply configured to operate at a frequency of about 1 KHz-2 MHz.
  - 9. (Original) A substrate processing chamber comprising:
  - a chamber body;
  - a chamber top disposed on the chamber body;
  - an alternating-current power supply; and
- a transformer-coupled plasma generator plate having a plurality of through holes forming conduits from a first side of the transformer-coupled plasma generator plate within the substrate processing chamber to a second side of the transformer-coupled plasma generator plate within the substrate processing chamber, a first portion of the conduits passing through centers of a plurality of toroidal transformer cores within the generator plate and a second portion of the conduits not passing through centers of transformer cores, the generator having a first surface comprising metal, a second surface comprising metal, and a plurality of dielectric spacers disposed between the first surface and the second surface in each of the first portion of the conduits.
  - 10. (Currently Amended) A plasma generator plate comprising:
  - a first side;
  - a second side;
- a first conduit passing from the first side to the second side through a first transformer core within the plasma generator plate;
- a second conduit passing from the first side to the second side through a second transformer core; and



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a third conduit passing from the first side to the second side not passing through a transformer core.

11. (Original) The plasma generator plate of claim 10 further comprising a first dielectric spacer in a first secondary current path around the first transformer core.

- 12. 17. (Canceled).
- 18. 20. (Withdrawn).
- 21. (Canceled).
- 22. 39. (Withdrawn).
- 40. (Canceled).
- 41. 45. (Withdrawn).
- 46. 48. (Canceled).
- 49. 50. (Withdrawn).
- 51. 52. (Canceled).